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PTO/SB/08B (10-96)
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Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Complete if Known	
		Application Number	09/375,627
		Filing Date	August 17, 1999
		First Named Inventor	Hans Loschner, et al.
		Group Art Unit	1756
		Examiner Name	Unknown
		Attorney Docket Number	99108
Sheet	2	of	3

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
AZ	1	"Characteristics And Applications Of Multiple Beam Machines", JULIUS J. MURAY, Microelectronic Engineering 9 (1989), pp. 305-309	
AZ	2	"Electron-beam microcolumns for lithography and related applications:", T.H.P. CHANG, ET AL., J.Vac.Sci.Technol.B 14(6), (Nov/Dec 1996), pp 3774-3781	
AZ	3	"An Approach To Multiple E-Beam System", NOBUO SHIMAZU, ET AL., Proceedings of the 'International Workshop On High Throughput Chaged Particle Lithography', Hawaii (August 11-15, 1997)	
AZ	4	"A New Focused Ion Beam System For Maskless Direct-write Lithography", Q. JI, ET AL., Proceedings of the 43rd International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication, (EIPBN 1999), Marco Island, Florida (June 1-4, 1999)	
AZ	5	"Distributed, multiple variable shaped electron beam column for high throughput maskless lithography", T.R. GROVES, ET AL., J. Bac.Sci.Technol.B 16(6), (Nov/Dec 1998) pp 3168-3173	
AZ	6	"Illumination and source requirements for a distributed-axis electron beam lithography system", D.S. PICKARD, ET AL., Proceedings of the EIPBN 1999	
AZ	7	"High throughput electron lithography with the multiple aperture pixel by pixel enhancement of resolution concept", P. KRUIT, J.Vac.Sci.Technol.B 16(6) (Nov/Dec 1998), pp 3177-3180	
AZ	8	"Capability of Ion Beam Projection Optics for Microfabrication", Y. MADOKORO, ET AL., Microelectronic Engineering 46 (1999), pp 493-496	
AZ	9	"Vakuumbeschichtung 1", HARTMUT FREY, VDI-Verlag, Dusseldorf, Germany (1995), Section 1.12.3, pp 154-162	
AZ	10	"Technology of ion beam sources used in sputtering", HAROLD R. KAUFMAN, J.Vac.Sci.Technol. 15(2), (March/April 1978), pp 272-276	

Examiner Signature	A. Zuck	Date Considered	1/22/01
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a.2	11	"Micromachined single-crystal silicon electron lenses", WOLFGANG HOFMAN, ET AL., J.Vac.Sci.Technol.B 15(6), (Nov/Dec 1997, pp 2713-2717	
a.2	12	"The electrostatic moving objective lens and optimized deflection systems for microcolumns", M.G.R. THOMSON, J.Vac.Sci.Technol. B 14(6), (Nov/Dec 1996), pp 3802-3807	
a.2	13	"ELECTROSTATUS LENSES", E. HARTING, ET AL., Elsevier Scientific Publishing Company, Amsterdam, The Netherlands, 1976, pp 175-176	
a.2	14	"Focusing of Charged Particles", ALBERT SEPTIER, Academic Press, New York, 1967, Vol. II, Chapter 3.1	
a.2	15	"Tabellen zur angewandten Physik", MANFRED VON ARDENNE, Veb Deutscher Verlag der Wissenschaften, Berlin, Germany, 1975, Volume 1, pp 9-13	

Examiner Signature	<i>a.2. Losch</i>	Date Considered	1/22/01
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